

Supporting Information:
Achieving Direct Band Gap and High Power
Conversion Efficiency in $\text{SbI}_3/\text{BiI}_3$ Type-II
vdW Heterostructure via Interlayer
Compression and Electric Field

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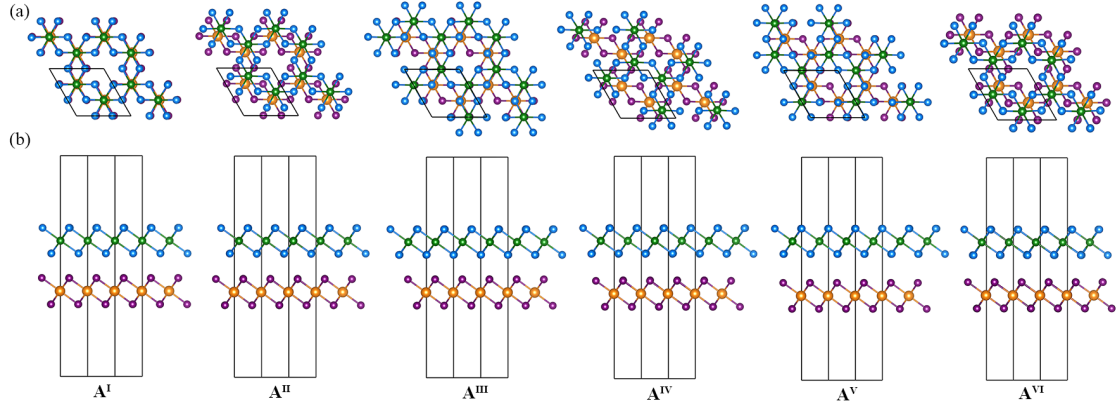


Figure S1: Top (a) and side (b) view of six selected configurations within $\text{SbI}_3/\text{BiI}_3$ moiré pattern A. The green, yellow, blue and purple balls represent Sb, Bi, and I atoms, respectively.

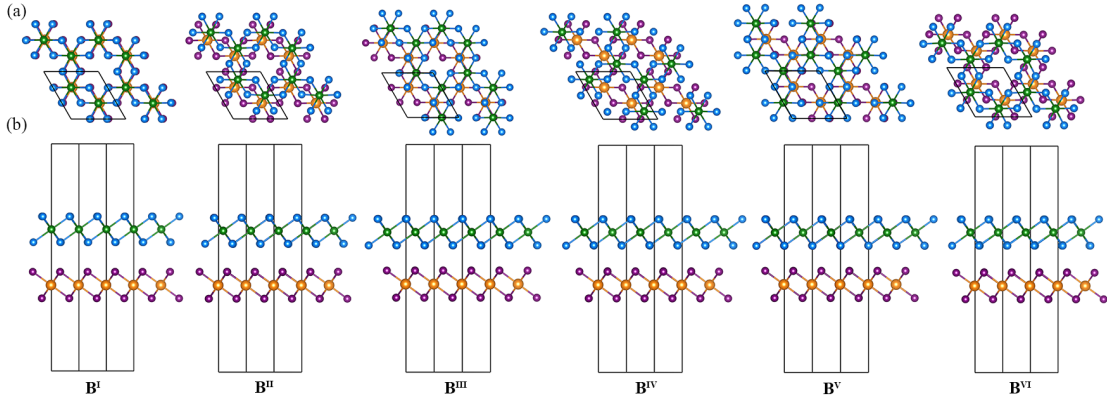


Figure S2: Top (a) and side (b) view of six selected configurations within $\text{SbI}_3/\text{BiI}_3$ moiré pattern B. The green, yellow, blue and purple balls represent Sb, Bi, and I atoms, respectively.

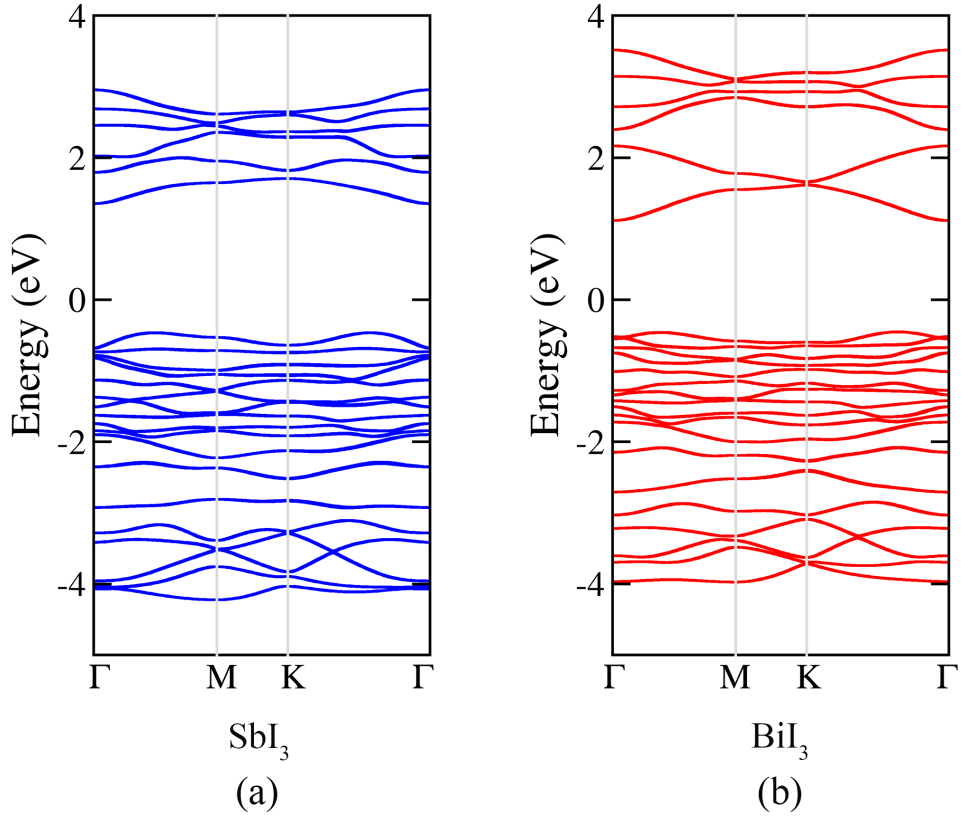


Figure S3: The electronic band structure of free-standing BiI_3 and stretched SbI_3 single-layer.

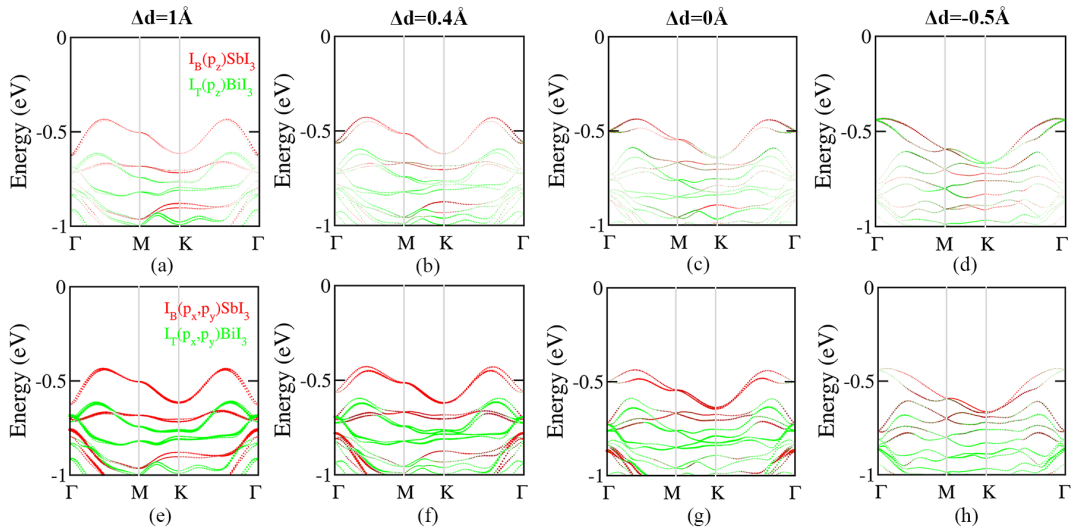


Figure S4: The orbitals-projected band structure of interlayer $I(p_z)$ states ((a)-(d)) and $I(p_x, p_y)$ states ((e)-(h)) with different interlayer distances.

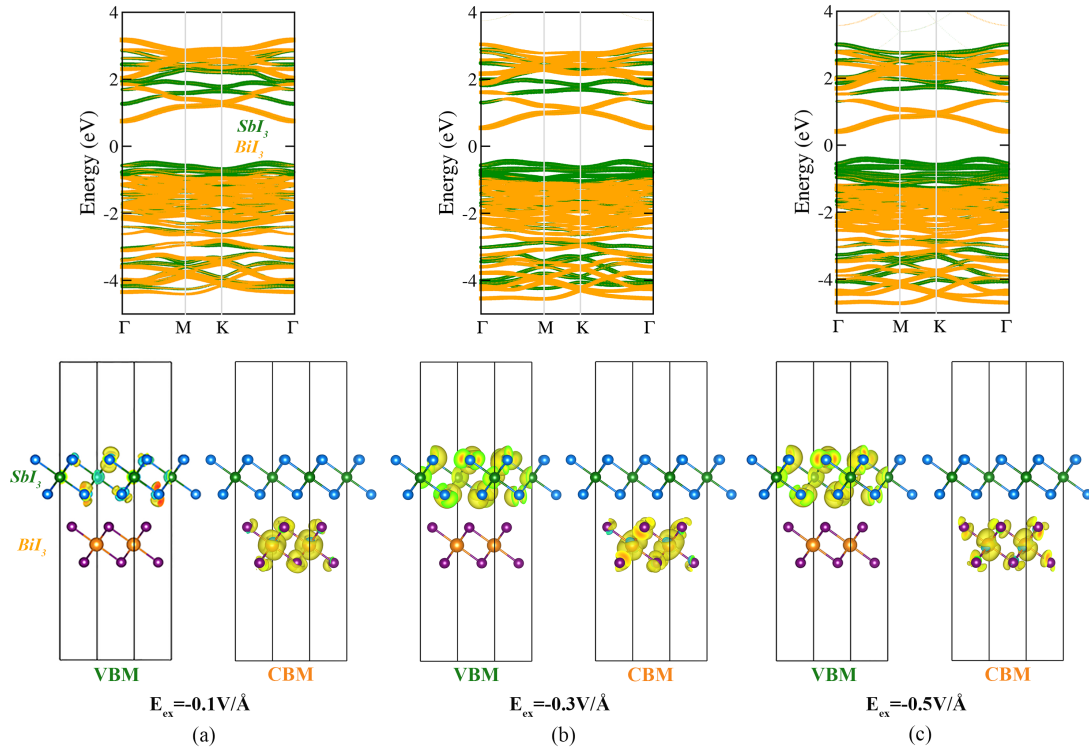


Figure S5: The layer-projected band structure and the isosurface of charge density of the VBM and CBM of $\text{SbI}_3/\text{BiI}_3$ vdW heterostructure under -0.1 (a), -0.3 (b) and $-0.5 \text{ V}/\text{\AA}$ (c) electric field. The value of isosurface is $0.00055 \text{ e}/\text{bohr}^3$.

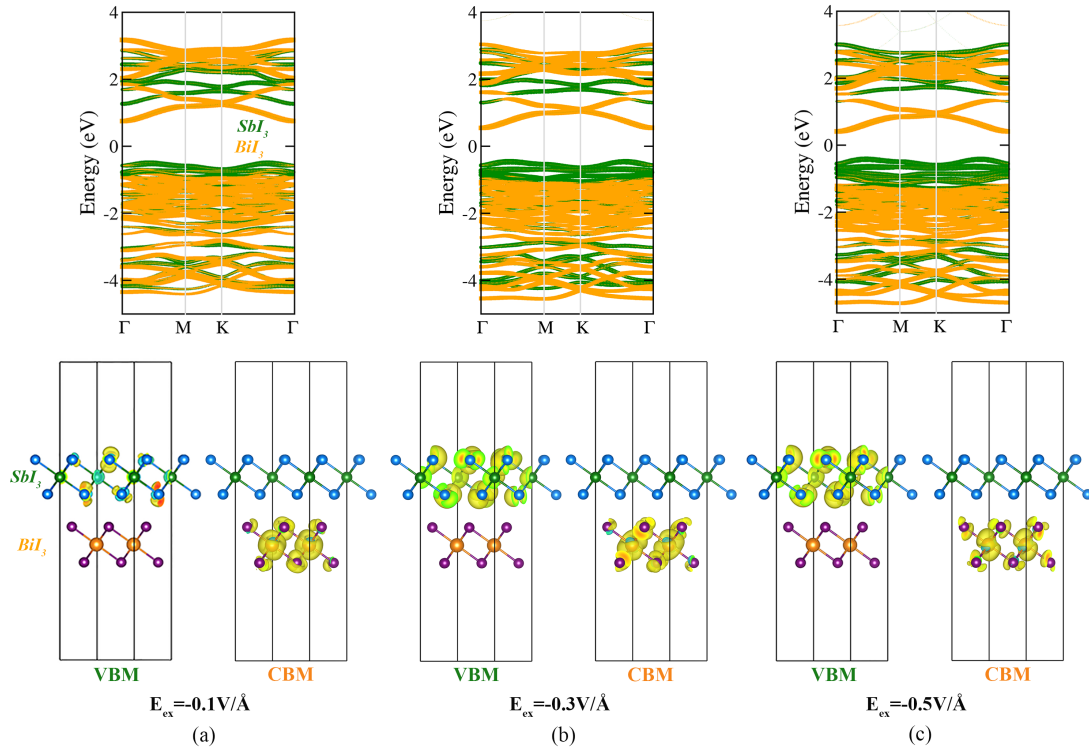


Figure S6: The layer-projected band structure and the isosurface of charge density of the VBM and CBM of $\text{SbI}_3/\text{BiI}_3$ vdW heterostructure under 0.1(a), 0.3(b) and 0.5 V/\AA (c) electric field. The value of isosurface is 0.00055 e/bohr^3 .